ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18 Stylesheet Version v18.0

Title of Invention

Method for forming silicon dioxide film using siloxane

Application Number :

10/782094 4756

Confirmation Number: First Named Applicant:

Jae-eun Park

(3313792).pn

Attorney Docket Number:

SAM-0483

Art Unit:

Examiner:

Search string:

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

init	Cite.No.	Patent No.	Date	Patentee	Kind	Class	Subclass
	1	3313792	1967-04-11	Duck, et al.			

Remarks

Note: Remarks are not for responding to an office action.

Part 1 of 1.

Signature

Examiner Name	Date